

ABSTRACT OF THE DISCLOSURE

It is disclosed a method of forming fine patterns comprising: subjecting a substrate having photoresist patterns
5 to a hydrophilic treatment, covering the substrate having photoresist patterns with an over-coating agent for forming fine patterns, applying heat treatment to cause thermal shrinkage of the over-coating agent so that the spacing between adjacent photoresist patterns is lessened by the re-
10 sulting thermal shrinking action, and removing the over-coating agent substantially completely.